INFULL (Indian (IN) Patents Full-Text)

Subject Coverage	All patent-relevant areas of science and technology, i.e., all classes of the International Patent Classification
File Type	Full-Text
Features	Thesauri: International Patent Classification (/IPC), Cooperative Patent Classification (/CPC), European Patent Classification (/EPC) Alerts (SDIs): Weekly or monthly (weekly is the default) CAS Registry Number® Identifiers ☐ SLART ☑ Structures ☐ Keep & Share ☑ Register Links ☑
Record Content	• Full-text of patent applications and granted patents in India from publication year 1912 onwards. • Records are available about a week after publication date with the complete content. • Records contain bibliographic data including patent applicant and inventor, patent, application, priority, and related application data, IPC, CPC, and EPC classification codes, abstract, and full-text of description and claims. • Abstracts are either original or taken from equivalent documents if available. If description and claims are not present in sufficient quality, they are taken from equivalent documents and indexed with DETD.EQ and/or CLM.EQ in the field availability (FA) index. • Standardized and normalized patent assignee names are searchable in their own fields /PAS and /PAN. • Independent claims and claim groups are searchable for all claims in English. • Numeric values of 59 physical and chemical properties are searchable in about 20,000 unit variants in all full-text fields. • Ultimate Owners are searchable in the field /UO and /UOS. • Key terms, indexed and displayed in the field /KT, enhance retrieval of relevant results, and make the evaluation of results more efficient. They are useful to broaden search scope more precisely than Basic Index searches. • Original application and publication numbers are indexed in the search fields application number, original (/APO) and patent number, original (/PNO) • Database records comprise all documents published for one application. • Bibliography and full-text have been created by Optical Character Recognition (OCR) software for many documents. A number of original documents are printed in poor quality and may cause misinterpretations of characters. Portions of the text may be incomplete.
File Size	• More than 1.23 million family records with more than 1.59 million publications (01/2026) • More than 780,000 front page images from 1975 to present (01/2026)
Coverage	1912–present; between 1912 and 1994, only granted patents (kind code A1) are available
Updates	Weekly
Language	English

January 2026

Database Producer	LexisNexis Business Information Solutions B.V. Radarweg 29 1043 NX Amsterdam The Netherlands Copyright Holder
Sources	Patent applications and granted patents published by the Intellectual Property Office in India
User Aids	• Online Helps (HELP DIRECTORY lists all help messages available) • STNGUIDE
Clusters	• AEROTECH • ALLBIB • AUTHORS • CORPSOURCE • ENGINEERING • FULLTEXT • HPATENTS • NPS • PATENTS • PNTTEXT STN Database Cluster information

Search and Display Field Codes

If multiple search terms are linked with and AND-operator, all terms are searched in the complete database record, i.e., in all publications referring to one application. For a search in a specific publication of the record, connect the search term and the patent kind code with the (L)-proximity operator, e.g.,
S BOREHOLE/AB,TI,CLM (L) INA/PK limits the search to Indian applications INA.
Fields that allow left truncation are indicated by an asterisk (*).

General Search Fields

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index* (contains single words from title (TIEN), abstract (ABEN), detailed description (DETDEN), claims (CLMEN), and main claims (MCLMEN), and key term (KT) fields)	None or /BI	S TRANSISTOR AND ELECTRODE S ACOUSTIC SENSOR S ?TRANSFER?	TIEN, AB, ABEN, DETD, DETDEN, CLM, CLMEN, MCLM, MCLMEN, KT
Abstract*	/AB	S BOREHOLE/AB	AB
Abstract (English)*	/ABEN	S BOREHOLE/ABEN	AB, ABEN
Accession Number	/AN	S 2011000109/AN	AN
Application Country (WIPO code and text)	/AC	S IN/AC	AI
Application Date **(1)**	/AD	S AD=JAN 2011	AI
Application Kind Code	/AK	S INA/AK	AI
Application Number **(2)**	/AP	S IN2010-CH1005/AP	AI
Application Number Original	/APO	S IN1005CHE2010/APO	APO
Application Year **(1)**	/AY	S AY>=2000	AI
Claims*	/CLM	S DERIVATION/CLM	CLM
Claims (English)*	/CLMEN	S DERIVATION/CLMEN	CLM, CLMEN
Claims, Claim Groups*	/CLM.CG	S OFFICE CHAIR/CLM.CG	CLM, CLM.CG
Claims, Independent Claims*	/CLM.IC	S OFFICE CHAIR/CLM.IC	CLM.IC, CLM, CLMEN
Cooperative Patent Classification **(3)**	/CPC	S C12N0009/CPC	CPC
Cooperative Patent Classification, Action Date **(1)**	/CPC.ACD	S 20121113/CPC.ACD	CPC.TAB
Cooperative Patent Classification, Keyword	/CPC.KW	S C12N0009/CPC (S) I/CPC.KW	CPC.TAB
Cooperative Patent Classification, Version	/CPC.VER	S 20130101/CPC.VER	CPC.TAB
CPC, Combination Set	/CPC.CS	S C08L0079-02/CPC.CS	CPC
Data Entry Date **(1)**	/DED	S 20120113/DED	DED
Data Update Date **(1)**	/DUPD	S 20120124/DUPD	DUPD
Detailed Description	/DETD	S *LASER/DETD	DETD, DETDEN
Detailed Description (English)	/DETDEN	S LASER LIGHT/DETDEN	DETDEN, DETD
Document Type (code and text)	/DT (or /TC)	S P/DT S PATENT/DT	DT
Entry Date **(1)**	/ED	S ED=MAY 2013	ED
Entry Date of Full-Text **(1)**	/EDTX	S 20130526/EDTX	EDTX
European Patent Classification **(3)**	/EPC (or /ECLA)	S H02K0003-12/EPC	EPC
EPC. Keyword	/EPC.KW	S K23G200/06/EPC.KW	EPC
Field Availability	/FA	S AB/FA	FA
International Patent Classification, Version 1-7 (ICA, ICI, ICM, ICS)	/IC	S A45D/IC	IC, ICM, ICS
International Patent Classification, Version 1-8 (ICM, ICS, IPCI, IPCR) **(3)**	/IPC	S A01B0001-10/IPC	ICM, ICS, IPCI, IPCR
Inventor	/IN (or /AU)	S CHADIVE RAJA REDDY/IN S PRAJNAN CHAITAN?/IN	IN
Inventor, Country (WIPO code and text)	/IN.CNY	S IN/IN.CNY	IN, IN.CNY
IPC Additional	/ICA (or /IPCA)	S C07C043-00/ICA	ICA
IPC Index	/ICI (or /IPCIN)	S B29K0307:04/ICI	CI, IPC, IC
IPC Initial	/IPCI	S B21B0001/IPCI	IPCI, IPC
IPC, Keyword Terms	/IPC.KW	S INITIAL/IPC.KW	IPC.TAB
IPC Main	/ICM	S A63B021-00/ICM	ICM, IC
IPC Reclassified	/IPCR	S B21D0007-08/IPCR	IPCR, IPC
IPC, Reform	/IPC.REF	S A01B0001-16/IPC.REF	IPC.TAB
IPC, Secondary	/ICS	S A41D027-04/ICS	ICS, IC
IPC, Version	/IPC.VER	S 7/IPC.VER	IPC.TAB

General Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Key Terms	/KT	S “GLUCOSE AND GALACTOSE ABSORPTION”/KT	KT
Language (code and text)	/LA	S EN/LA	LA
Language of Filing (code and text)	/LAF	S ENGLISH/LAF	LAF
Main Claim*	/MCLM	S ?FRACTURE?/MCLM	MCLM
Main Claim (English)*	/MCLMEN	S ?FRACTURE?/MCLMEN	MCLMEN, MCLM
Number of Claims **(1)**	/CLMN	S 5-7/CLMN	CLMN
Number of Paragraphs in DETD (Detailed Description) **(1)**	/DETN	S DETN<10	DETN
Patent Assignee **(4)**	/PA (or /CS)	S ARCELOR MITTAL/PA	PA
Patent Assignee, Country	/PA.CNY	S IN/PA.CNY	PA, PA.CNY
Patent Assignee, Total **(4)**	/PA.T	S SAMSUNG AEROSPACE INDUSTRIES, LTD./PA	PA
Patent Assignee Normalized (4)	/PAN	S SAMSUNG/PAN	PAN
Patent Assignee Standardized **(4)**	/PAS	S SAMSUNG AEROSPACE INDUSTRIES/PAS	PAS
Patent Country (WIPO code and text)	/PC	S IN/PC	PI
Patent Information Type	/PIT	S INA APPLICATION /PIT	PIT
Patent Kind Code	/PK	S INA/PK	PI
Patent Number **(2)**	/PN	S IN2000CH00043/PN	PI
Patent Number Original	/PNO	S IN10005DELNP2007/PNO	PNO
Patent Number/Kind Code	/PNK	S IN2005CH00024 A/PNK	PI
Patent Status Established Date	/STED	S 20250227/STED	STED
Patent Status Indicator	/STI	S A/STI	STI
Physical Properties	/PHP	S PHV/PHP (S) BUFFER/BI	KWIC
Priority Country (WIPO code and text)	/PRC	S IN/PRC S INDIA/PRC	PRN
Priority Date **(1)**	/PRD	S PRD=MAY, 20 2003 S 20030520/PRD	PRN
Priority Date First **(1)**	/PRDF	S 20010614/PRDF	PRN
Priority Number **(2)**	/PRN	S DE2004-202004000592/PRN	PRN PRNO, PRAO
Priority Number Original	/PRNO	S US10061642/PRNO	PRN
Priority Year **(1)**	/PRY	S 2003/PRY	PRN
Priority Year First **(1)**	/PRYF	S 2003-2004/PRYF	PRN
Publication Date **(1)**	/PD	S PD=MARCH-APRIL 2011	PI
Publication Year **(1)**	/PY	S PY>2008 AND L1	PI
Related Application Country	/RLC	S WO/RLC	RLI
Related Application Date **(1)**	/RLD	S 20050330/RLD	RLI
Related Application Number	/RLN	S WO2005-JP24280/RLN	RLI
Related Application Type	/RLT	S PCT APPLICATION/RLT	RLI
Related Application Year **(1)**	/RLY	S 2005/RLY	RLI
Related Patent Country	/RLPC	S WO/RLPC	RLI
Related Patent Number **(2)**	/RLPN	S WO2000000071/RLPN	RLI
Related Publication Date **(1)**	/RLPD	S 20210805/RLPD	RLI
Related Publication Year **(1)**	/RLPY	S 2019/RLPY	RLI
Title*	/TI	S LASER/TI	TI
Title (English)*	/TI	S FLUID###/TIEN	TI, TIEN
Ultimate Owner **(4)**	/UO	S INA/UO	UO
Ultimate Owner Standardized **(4)**	/UOS	S INA/UOS	UOS
Update Date **(1)**	/UP	S UP=JUNE 2013/UP	UP
Update Date Full-Text **(1)**	/UPTX	S UP=JUNE 2013/UPTX	UPTX

(1) Numeric search field that may be searched using numeric operators or ranges.
(2) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(3) An online thesaurus is available in this field.
(4) Search with implied (S) proximity is available in this field.

Super Search Fields

Enter a super search code to execute a search in one or more fields that may contain the desired information. Super search fields facilitate crossfile and multifile searching. EXPAND may not be used with super search fields. Use EXPAND with the individual field codes instead.

Search Field Name	Search Code	Fields Searched	Search Examples	Display Codes
Application Number Group	/APPS	AP, APO, PRN, PRNO, RLN	S IN2011-CH1006/APPS	AI, APO, PRAI, RLI, APPS
Patent Assignee Group	/PASS	PA, PA.T, PAS, PAN, UO	S SAMSUNG/PASS	PA, PAS, PAN, UO, PASS
Patent Number Group	/PATS	PN, PNO, RLPN	S IN1399575/PATS	PN, RLPN, PNO, PATS

Property Fields (1)

In INFULL a numeric search for a specific set of physical properties (/PHP) is available within the full-text fields (TI, AB, DETD, and CLM). The numeric values are not displayed as single fields, but highlighted within the hit displays.
Use EXPAND/PHP to search for all available physical properties. A search with the respective field codes will be carried out in all database fields with English text. The /PHP index contains a complete list of codes and related text for all physical properties available for numeric search.

Field Code	Property	Unit	Symbol	Search Examples
/AOS	Amount of substance	Mol	mol	S 10 /AOS
/BIR	Bit Rate	Bit/Second	bit/s	S 8000-10000/BIR
/BIT	Stored Information	Bit	Bit	S BIT > 3 MEGABIT
/CAP	Capacitance	Farad	F	S 1-10 MF/CAP
/CATA	Catalytic Activity	Katal	kat	S 1-10/CATA
/CDN	Current Density	Ampere/Square Meter	A/m^2	S CDN>10 A/M**2
/CMOL	Molarity, Molar Concentration	Mol/Liter	mol/L	S UREA/BI (S) 8/CMOL
/CON	Electrical Conductance	Siemens	S	S 1S-3/CON
/DB	Decibel	Decibel	dB	S DB>50
/DEG	Degree	Degree	°	S CYLINDER/BI (S) 45/DEG
/DEN (/C)	Density (Mass Concentration	Kilogram/Cubic Meter	kg/m^3	S 5E-3-10E-3/DEN
/DEQ	Dose Equivalent, Absorbed Dose	Sievert	Sv	S 100/DEQ
/DOA	Dosage	Milligram/Kilogram/Day	mg/kg/day	S 100-300/DOA
/DOS (/LD50)	Dose	Milligram/Kilogram	mg/kg	S DOS>0.8
/DV	Viscosity, dynamic	Pascal * Second	Pa * s	S DV>5000
/ECH (/CHA)	Electric Charge, Capacity	Coulomb	C	S 0.0001-0.001/ECH
/ECO (/ECND)	Electrical Conductivity	Siemens/Meter	S/m	S ECO>800 S/M (15A) AQUEOUS
/ELC (/ECC)	Electric Current	Ampere	A	S 1-10/ELC
/ELF (/ECF)	Electric Field	Volt/Meter	V/m	S 200/ELF
/ENE	Energy	Joule	J	S DROPLETS (10A) 40 JOULE - 70 JOULE /ENE
/ERE (/ERES)	Electrical Resistivity	Ohm * Meter	Ohm * m	S ERE>0.1
/FOR	Force	Newton	N	S 50 N /FOR
/FRE (/F)	Frequency	Hertz	Hz	S OSCILLAT?/BI (S) 1- 3/FRE
/IU	International Unit	none	IU	S IU>1000 (P) VITAMIN A
/KV	Viscosity, kinematic	Square Meter/Second	m2/s	S METHYLPOLYSILOXANES/BI (10A) 200-300 CST /KV
/LEN (/SIZ)	Length, Size	Meter	m	S 1-4/LEN
/LUME	Luminous Emittance, Illuminance	Lux	lx	S 10-50/LUME
/LUMF	Luminous Flux	Lumen	Lm	S LUMF>1000

Property Fields (1) (cont'd)

Field Code	Property	Unit	Symbol	Search Examples
/LUMI	Luminous Intensity	Candela	cd	S LUMI<4
/M	Mass	Kilogram	kg	S ALLOY/BI (30A) 1E-10-1E-5/M
/MCH	Mass to Charge Ratio	none	m/z	S MCH=1
/MFD (/MFS)	Magnetic Flux Density	Tesla	T	S MFD>102
/MFR (/MFL)	Mass Flow Rate	Kilogram/Second	kg/s	S MFR<0.1
/MFST	Magnetic Field Strength	Ampere/Meter	A/m	S MFST/PHP
/MM (/MW, /MOM)	Molar Mass, Molecular Weight	Gram/Mol	g/mol	S 2000-3000 G/MOL/MM
/MOLS	Molality of Substance	Mol/Kilogram	mol/kg	S 01.-10 MOL/KG/MOLS
/MVR	Melt Volume Rate, Melt Flow Rate	none	g/10 min	S 3/MVR
/PER	Percent (Proportionality)	none	%	S POLYMER?/AB (5A) 4/PER
/PHV (/PH)	pH Value	pH	pH	S 7.4-7.6/PHV
/POW (/PW)	Power	Watt	W	S "HG-XE-?"/BI (S) 100-200 WATT/POW
/PPM	Parts per million	Ppm	ppm	S 100 PPM /PPM (10A) ADDITIVE/BI
/PRES (/P)	Pressure	Pascal	Pa	S (VACUUM (5A) DISTILL?)/BI (S) 1000-1100/PRES
/RAD	Radioactivity	Becquerel	Bq	S RAD/PHP
/RES	Electrical Resistance	Ohm	Ohm	S SENSOR /BI (S) 10- 100/RES
/RI	Refractive Index	none	none	S 3-4/RI
/RSP	Rotational Speed	Revolution/Minute	rpm	S 2 RPM - 100 RPM /RSP (S) ENGINE/BI
/SAR	Area	Square Meter	m²	S PLATE/BI (S) 10 M**2 - 100 M**2 /SAR
/SOL (/SLB)	Solubility	Gram/100 gram	g/100 g	S SOL>20 G/100G (5A) WATER
/SSAM	Specific Surface Area, Mass	Square Meter/ Kilogram	m2/kg	S 1-10/SSAM
/STSC (/ST)	Surface Tension, Spring Constant	Joule /Square Meter	J/m²	S 60 J/M**2/STSC
/TCO (/TCND)	Thermal Conductivity	Watt/Meter * Kelvin	W/m * K	S 1/TCO (S) HEAT?
/TEMP (/T)	Temperature	Kelvin	K	S 20-25/TEMP
/TEX	Tex	Gram/Kilometer	g/km	S 1-5/TEX
/TIM	Time	Second	s	S ?INCUB?/BI (10A) 50 S - 150 S /TIM
/VEL (/V)	Velocity	Meter per Second	m/s	S REDUC?/BI (S) 1E-3-5E-3/VEL
/VELA	Velocity, angular	Radian/Second	rad/s	S VELA>10
/VLR	Volumetric Flow Rate	Cubic Meter/Second	m³/s	S 1 M**3/S - 2 M**3/S /VLR (S) ABRASIVE
/VOL	Volume	Cubic Meter	m³	S 1E-8-2E-8/VOL.EX
/VOLT	Voltage	Volt	V	S TENSION/BI (10A) 5E-3 V <VOLT<7E-3 V

(1) Exponential format is recommended for the search of particularly high or low values, e.g., 1.8E+7 or 1.8E7 (for 18000000) or 9.2E-8 (for 0.000000092).

International Patent Classification (/IPC) Thesaurus

The classifications, validity and catchwords for the main headings and subheadings from the current (8th) edition of the WIPO International Patent Classification (IPC) manual are available. The classifications from the previous editions (1-7) are also available as separate thesauri. To EXPAND and SEARCH in the thesauri for editions 1–7, use the field code followed by the edition number, e.g., /IPC2, for the 2nd edition. Catchwords are included only in the thesauri for the 8th, 7th, 6th, and 5th editions.

Relationship Code	Content	Examples
ADVANCED /ADV)	Advanced Codes for the Core Level IPC Code	E A61K0006-06+ADVANCED/IPC
ALL	All Associated Terms (BT, SELF, NT, RT)	E C01C003-00+ALL/IPC
BRO (MAN)	Complete Class	E C01C+BRO/IPC
BT	Broader Term (BT, SELF)	E C01F001-00+BT/IPC
CORE (COR)	Core Codes for the Advanced Level IPC Code	E G08C0019-22+CORE/IPC
ED	Complete title of the SELF term and IPC manual edition	E C01F001-00+ED/IPC
HIE	Hierarchy Term (Broader and Narrower Term) (BT, SELF, NT)	E C01B003-00+HIE/IPC
INDEX	Complete title of the SELF term	E C01F001-00+INDEX/IPC
KT	Keyword Term (catchwords) (SELF, KT)	E CYANOGEN+KT/IPC
NEXT	Next Classification	E C01C001-00+NEXT5/IPC
NT	Narrower Terms (SELF, NT)	E C01C+NT/IPC
PREV	Previous Classification	E C01C001-12+PREV10/IPC
RT (SIB)	Related Terms (SELF, RT)	E C01C003-20+RT/IPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E C01F001-00+TI/IPC

ECLA (/EPC) and Thesaurus

This thesaurus is available in the /EPC search field for ECLA codes. All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL	All usually required terms (BT, SELF, CODE, DEF)	E C12M0001-34H2+ALL/EPC
AUTO **(1)**	Automatic relationship (BT, SELF, CODE, DEF)	E G01N0033-50D4 +AUTO/EPC
BT	Broader terms (BT, SELF)	E G01N0033-50D4 +BT/EPC
CODE	Classification Code (SELF, CODE)	E SCRAPER BIASING MEANS+CODE/EPC
DEF	Definition (SELF, DEF)	E B65G0045-16+DEF/EPC
HIE	Hierarchy terms (all broader and narrower terms) (BT, SELF, DEF, NT)	E A01C0001-06+HIE/EPC
KT	Keyword terms (SELF, KT)	E LASER+KT/EPC
MAX	All associated terms	E G01N0033-50D4+MAX/EPC
NEXT	Next classification within the same class (SELF, NEXT)	E A01C0001-06+NEXT/EPC
NEXT(n)	Next n classification within the same class	E A01C0001-06+NEXT3/EPC
NT	Narrower terms	E G05B0019-10+NT/EPC
PREV	Previous Code within the same class (SELF, PREV)	E G05B0019-10+PREV/EPC
PREV(n)	Previous n classifications within the same class	E G05B0019-10+PREV2/EPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E G05B0019-10+TI/EPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON, the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

CPC Thesaurus

This thesaurus is available in the /CPC search field. All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL	All usually required terms (BT, SELF, CODE, DEF)	E A61K0031-4375+ALL/CPC
AUTO **(1)**	Automatic relationship (BT, SELF, CODE, DEF)	E C07D0473-40+AUTO/CPC
BT	Broader terms (BT, SELF)	E C12N0009-6464+BT/CPC
CODE	Classification Code (SELF, CODE)	E CARTRIDGES+CODE/CPC
DEF	Definition (SELF, DEF)	E B65G0045-16+DEF/CPC
HIE	Hierarchy terms (all broader and narrower terms) (BT, SELF, DEF, NT)	E F02M0031-047+HIE/CPC
KT	Keyword terms (SELF, KT)	E LASER+KT/CPC
MAX	All associated terms	E G01R0022-066+MAX/CPC
NEXT	Next classification within the same class (SELF, NEXT)	E A01N0041-04+NEXT/CPC
NEXT(n)	Next n classification within the same class	E A01N0041-04+NEXT3/CPC
NT	Narrower terms	E C07D0473-40+NT/CPC
PREV	Previous Code within the same class (SELF, PREV)	E F05C2253-16+PREV/CPC
PREV(n)	Previous n classifications within the same class	E F05C2253-16+PREV2/CPC
TI	Complete Title of SELF Term and Broader Terms (BT, SELF)	E F05B2250-313+TI/CPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON, the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

DISPLAY and PRINT Formats

Any combination of formats may be used to display or print answers. Multiple codes must be separated by spaces or commas, e.g., D L1 1-5 TI PA. The fields are displayed or printed in the order requested.
The information of the latest publication is displayed by default. To display the content for all levels of the record you can combine all display fields and formats with the qualifier .M except FA, SCAN, and TRIAL.
For displaying a particular publication of a database record, you can simply add for certain display field the kind code to the appropriate display format, e.g., ALL.A. Fields that allow this are indicated by a number (3).
Hit-term highlighting is available for all fields. Highlighting must be ON during SEARCH to use the HIT, KWIC, and OCC formats. The default display format is STD.M, i.e., all publication levels of one family in the STD format.

Format	Content	Examples
AB (ABS)	Abstract	D TI AB 1-5
ABEN	Abstract (English)	D ABEN
AI (AP) **(1)**	Application Information	D AI
AN	Accession Number	D L3 AN
APO	Application Number Original	D APO
CLM **(3)**	Claims	D CLM
CLM.CG **(3)**	Claims, Claim Groups	D CLM.CG
CLM.IC **(3)**	Claims, Independent Claims	D CLM.IC
CLMEN **(3)**	Claims (English)	D CLMEN
CLMN **(2)**	Number of Claims	D CLMN
CPC	Cooperative Patent Classification	D CPC
DED	Data Entry Date	D DED
DETD **(3)**	Detailed Description	D DETD
DETDEN **(3)**	Detailed Description (English)	D DETDEN
DETN **(2)**	Number of Paragraphs in DETD	D DETN
DT (TC)	Document Type	D DT
DUPD	Data Update Data	D DUPD
ED	Entry Date	D ED
EDP	Entry Date Patent	D EDP
EDTX	Entry Date of Full-Text	D EDTX
EPC	European Patent Classification	D EPC
FA	Field Availability (for all publication levels)	D FA
GI	Graphic Image	D GI
IC	International Patent Classification, Version 1-7 (ICA, ICI, ICM, ICS)	D IC
ICA	IPC Additional	D ICA
ICI	IPC Index	D ICI
ICM	IPC Main	D IC

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
ICS	IPC Secondary	D ICS
IN (AU)	Inventor (English)	D IN
IN.CNY	Inventor, Country	D IN.CNY
IPC	International Patent Classification, Version 1-8 (ICA, ICI, ICM, ICS, IPCI, IPCR)	D IPC
IPCI	IPC Initial	D IPCI
IPCR	IPC Reclassified	D IPCR
KT	Key Terms	D KT
LA	Language	D LA
LAF	Language of Filing	D LAF
MCLM	Main Claim	D MCLM
MCLMEN	Main Claim (English)	D MCLMEN
PA (CS)	Patent Assignee	D PA
PA.CNY	Patent Assignee, Country	D PA.CNY
PAN	Patent Assignee Normalized	D PAN
PAS	Patent Assignee Standardized	D PAS
PI (PN) **(1)**	Patent Information	D PI
PIT	Patent Information Type	D PIT
PNO	Patent Number Original	D PNO
PRN (PRAI) **(1,5)**	Priority Information	D PRN
PRNO (PRAO) **(2)**	Priority Number Original	D PRNO
RLI (RLN)	Related Patent Information	D RLI
RLPI	Related Patent Information	D RLPI
STED	Patent Status Established Date	D STED
STI	Patent Status Indicator	D STI
TI	Title	D TI
TIEN	Title (English)	D TIEN
UO	Ultimate Owner	D UO
UOS	Ultimate Owner Standardized	D UOS
UP	Update Date	D UP
UPTX	Update Date Full-Text	D UPTX
ALL **(1)**	AN, EDP, ED, UP, EDTX, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, UO, UOS, LAF, LA, DT, PI, PIT, STI, AI, PRAI, RLI, RLPI, ICA, ICI, ICM, ICS, IPCI, IPCR, CPC, EPC, ABEN, DETDEN, CLMEN, KT	D ALL
ALLG **(1)**	ALL, plus graphic image	D ALLG
DALL **(1)**	ALL, delimited for post processing	D DALL
IALL	ALL, indented with text labels	D IALL
IALLG **(1)**	IALL, plus graphic image	D IALLG
APPS **(1)**	AI, RLN, PRAI	D APPS
BIB **(1)**	AN, EDP, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, UO, UOS, LAF, LA, DT, PI, PIT, STI, AI, PRAI, RLI, RLPI	D BIB
BIBG **(1)**	BIB, plus graphic image	D BIBG
IBIB **(1)**	BIB, indented with text labels	D IBIB
IBIBG **(1)**	IBIB, plus graphic image	D IBIBG
BRIEF **(1)**	AN, EDP, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, UO, UOS, LAF, LA, DT, PI, PIT, STI, AI, PRAI, RLI, RLPI,ICA, ICI, ICM, ICS, IPCI, IPCR, CPC, EPC, ABEN, MCLMEN, KT	D BRIEF
BRIEFG **(1)**	BRIEF, plus graphic image	D BRIEFG
IBRIEF **(1)**	BRIEF, indented with text labels	D IBRIEF
IBRIEFG **(1)**	IBRIEF, plus graphic image	D IBRIEFG
CPC.TAB	CPC, CPC.KW, CPC.VER, CPC.ACD in tabular version	D CPC.TAB
IND	ED, IPC (ICM, ICS, IPCI, IPCR), CPC, EPC	D IND
IPC	International Patent Classification (ICM, ICS, IPCI, IPCR)	D IPC
IPC.TAB	IPC, IPC.KW, IPC.VER, IPC.ACD in tabular version	D IPC.TAB
MAX (ALL.M) **(1)**	AN, EDP, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, UO, UOS, LAF, LA, DT, PI, PIT, STI, AI, PRAI, RLI, RLPI, ICM, ICS, IPCI, IPCR, CPC, EPC, ABEN, DETDEN, CLMEN, KT, FA, from all publication levels	D MAX
MAXG (ALLG.M) **(1)**	MAX, plus graphic image	D MAXG
IMAX (IALL.M) **(1)**	MAX, indented with text labels	D IMAX
IMAXG (IALLG.M) **(1)**	IMAX, plus graphic image	D IMAXG
SCAN **(4)**	TI (random display without answer numbers)	D SCAN
STD **(1)**	AN, EDP, ED, EDTX, UP, UPTX, DED, DUPD, TIEN, IN, PA, PAS, PAN, UO, UOS, LAF, LA, DT, PI, PIT, STI, AI, PRAI, RLI, RLPI, ICA, ICI, ICM, ICS, IPCI, IPCR, CPC, EPC (STD.M is default)	D STD

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
STDG **(1)**	STD, plus graphic image	D STDG
ISTD **(1)**	STD, indented with text labels	D ISTD
ISTDG **(1)**	ISTD, plus graphic image	D ISTDG
TRIAL (TRI, SAM, SAMPLE, FREE)	EDP, ED, EDTX, UP, TI, FA, DETN, CLMN	D TRIAL
TX	DETDEN, CLMEN	D TX
HIT	Hit term(s) and field(s)	D HIT
KWIC	Up to 50 words before and after hit term(s) (KeyWord-In-Context)	D KWIC
OCC	Number of occurrences of hit term(s) and field(s) in which they occur	D OCC

(1) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(2) Custom display only.
(3) You can combine this display field with the qualifier .PK (Patent Kind Code) to display the content for a certain publication level of a record, e.g., CLM.B2.
(4) SCAN must be specified on the command line, i.e., D SCAN or DISPLAY SCAN.
(5) If priority information is not available for a certain document, this information is taken from the application information of this document and marked with an asterisk (*).

SELECT, ANALYZE, and SORT Fields

The SELECT command is used to create E-numbers containing terms taken from the specified field in an answer set.

The ANALYZE command is used to create an L-number containing terms taken from the specified field in an answer set.

The SORT command is used to rearrange the search results in either alphabetic or numeric order of the specified field(s).

You can combine all fields except FA with the qualifier .M to SELECT/ANALYZE the content of all publication levels.

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Abstract	AB	Y	N
Abstract (English)	ABEN	Y	N
Accession Number	AN	Y	Y
Application Country	AC	Y	Y
Application Date	AD	Y	Y
Application Information	AI (AP)	Y **(2)**	Y
Application Kind Code	AK	Y **(3)**	Y
Application Number Group	APPS	Y **(2)**	Y
Application Number Original	APO	Y	Y
Application Year	AY	Y	Y
Cooperative Patent Classification (CPC)	CPC	Y	Y
Data Entry Date	DED	Y	Y
Data Update Date	DUPD	Y	Y
Document Type	DT	Y	Y
Entry Date	ED	Y	Y
Entry Date Full-Text	EDTX	Y	Y
Entry Date Patent	EDP	Y	Y
European Patent Classification	EPC	Y	Y
Field Availability	FA	Y	N
International Patent Classification (ICA, ICI, ICM, ICS)	IC	Y	N
Inventor	IN (AU)	Y	Y
Inventor, Country	IN.CNY	Y	Y
IPC (ICM, ICS, ICA, ICI, IPCI, IPCR)	IPC	Y	Y
IPC, Advanced Level Symbols	IPC.A	Y **(4)**	N
IPC, Advanced Level Symbols for Invention	IPC.AI	Y **(4)**	N
IPC, Reclassified	IPCR	Y	Y
IPC, Reform	IPC.REF	Y	N
IPC Additional	ICA	Y	

SELECT, ANALYZE, and SORT Fields (cont'd)

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
IPC Index	ICI	Y	Y
IPC Initial	IPCI	Y	Y
IPC Main	ICM	Y	Y
IPC Secondary	ICS	Y	Y
Key Terms	KT	Y	N
Language	LA	Y	Y
Language of Filing	LAF	Y	Y
Number of Claims	CLMN	Y	Y
Number of Paragraphs in DETD	DETN	Y	Y
Occurrence Count of Hit Terms	OCC	N	Y
Patent Assignee	PA (CS)	Y	Y
Patent Assignee, Country	PA.CNY	Y	Y
Patent Assignee Address	PAA	Y	N
Patent Assignee Normalized	PAN	Y	Y
Patent Assignee Standardized	PAS	Y	Y
Patent Country	PC	Y	Y
Patent Information	PN (PI)	Y **(2)** (default)	Y
Patent Information Type	PIT	Y	Y
Patent Kind Code	PK	Y	Y
Patent Number Group	PATS	Y **(2)**	Y
Patent Number Original	PNO	Y	Y
Patent Number/Kind Code	PNK	Y	Y
Patent Status Established Date	STED	Y	Y
Patent Status Indicator	STI	Y	Y
Pre-IPC8 Symbols from the ICM and first IPC8 values from 2006-present	IPC.F	Y **(4)**	Y
Priority Country	PRC	Y	Y
Priority Date	PRD	Y	Y
Priority Date First	PRDF	Y	Y
Priority Number	PRN (PRAI)	Y **(2)**	Y
Priority Number Original	PRNO	Y	Y
Priority Year	PRY	Y	Y
Priority Year First	PRYF	Y	Y
Publication Date	PD	Y	Y
Publication Year	PY	Y	Y
Related Application Country	RLC	Y	Y
Related Application Date	RLD	Y	Y
Related Application Number	RLN	Y	Y
Related Application Type	RLT	Y	N
Related Application Year	RLY	Y	Y
Related Patent Country	RLPC	Y	Y
Related Patent Number	RLPN	Y **(2)**	Y
Related Publication Date	RLPD	Y	Y
Related Publication Year	RLPY	Y	Y
Title	TI	Y	Y
Title (English)	TIEN	Y	Y
Ultimate Owner	UO	Y	Y
Ultimate Owner Standardized	UOS	Y	Y
Update Date	UP	Y	Y
Update Date Full-Text	UPTX	Y	Y

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g., SEL HIT TI.
(2) Selects or analyzes application numbers with /AP appended to the terms created by SELECT.
(3) Appends /BI to the terms created by SELECT.
(4) Appends /IPC to the terms created by SELECT.

Sample Records

DISPLAY BIBG.M

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AN      1161863   INFULL  EDP 20200107  ED 20200107 UP 20250311 EDTX 20200107
        UPTX 20231010
        DED 20191223 DUPD 20250401 Full-text
TIEN    A HYBRID EXCITED INDUCTOR ALTERNATOR TO ACHIEVE WIDE FLUX REGULATION
IN      Uday Kumar Mudhigollam; Uppuluri Sridhar
PA      BHARAT HEAVY ELECTRICALS LIMITED, Regional office: Regional Operations
        Division (ROD), Plot No.: 9/1, DJ Block 3rd Floor, Karunamoyee, Salt
        Lake, Kolkata, West Bengal-700091, India. Registered Office: BHEL House,
        Siri Fort, New Delhi-110049, IN
PAS     BHARAT HEAVY ELECTRICALS
LAF     English
LA      English
DT      Patent; (Fulltext)
PI      IN 201831020794        A     20191206
PIT     INA ORDINARY PATENT APPLICATION or CONVENTION PATENT APPLICATION or PCT
        NATIONAL PHASE APPLICATION
STI     ALIVE
AI      IN 2018-31020794               20180604
PRAI    IN 2018-31020794               20180604
GI
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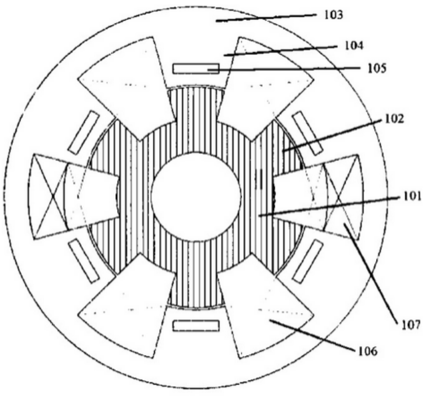

FIG. 1

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AN      1161863   INFULL  EDP 20200107  ED 20210622 UP 20210622 EDTX 20200107
        UPTX 20210615
        DED 20210604 DUPD 20210616 Full-text
TIEN    A HYBRID EXCITED INDUCTOR ALTERNATOR TO ACHIEVE WIDE FLUX REGULATION
PA      BHARAT HEAVY ELECTRICALS LIMITED
PAS     BHARAT HEAVY ELECTRICALS
LAF     English
LA      English
DT      Patent; (Fulltext)
PI      IN 367978              B     20210604
PIT     INB PATENT
STI     ALIVE
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PRAI    IN 2018-31020794               20180604
GI
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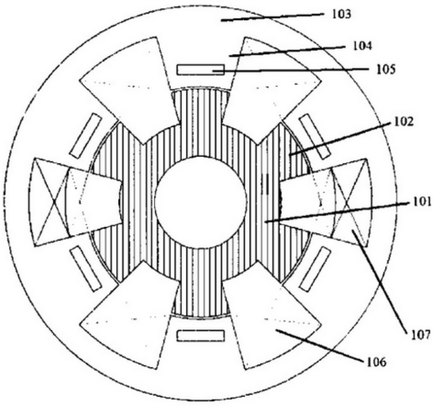

FIG. 1

DISPLAY ISTD.M

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AN      1159864   INFULL  EDP 20200317  ED 20200317 UP 20250304 EDTX 20200324
        UPTX 20230327
        DED 20200313 DUPD 20250225 Full-text
TIEN    SYSTEM AND METHOD FOR INCORPORATING A UNIDIRECTIONAL POINT TO MULTIPOINT
        CHANNELS IN WIRELESS BROADBAND NETWORK
IN      Parag Naik; Arindam Chakraborty; Makarand Kulkarni; Anindya Saha
PA      Saankhya Labs Pvt. Ltd., EMBASSY ICON, FLOOR-3, NO:3, INFANTRY ROAD, Dr.
        AMBEDKAR VEEDHI, Bangalore-560 001, India. Karnataka India
PAS     SAANKHYA LABS PVT
UO      TATA FAMILY TRUST
UOS     Tata Sons
LAF     English
LA      English
DT      Patent; (Fulltext)
PI      IN 201841034480        A     20200313
PIT     INA ORDINARY PATENT APPLICATION or CONVENTION PATENT APPLICATION or PCT
        NATIONAL PHASE APPLICATION
STI     ALIVE
AI      IN 2018-41034480               20180912
PRAI    IN 2018-41034480               20180912
IPCR    H04L0045-28 [I,A]
CPC     H04W0036-22; H04W0028-06; H04W0028-088; H04W0012-033; H04W0028-08;
        H04W0028-086; H04W0028-0861; H04W0048-18

AN      1159864   INFULL  EDP 20200317  ED 20230314 UP 20230328 EDTX 20200324
        UPTX 20230302
        DED 20220903 DUPD 20230322 Full-text
TIEN    SYSTEM AND METHOD FOR INCORPORATING A UNIDIRECTIONAL POINT TO MULTIPOINT
        CHANNELS IN WIRELESS BROADBAND NETWORK
PA      Saankhya Labs Pvt. Ltd.
PAS     SAANKHYA LABS
LAF     English
LA      English
DT      Patent; (Fulltext)
PI      IN 405057              B     20220902
PIT     INB PATENT
STI     ALIVE
AI      IN 2018-41034480               20180912
PRAI    IN 2018-41034480               20180912
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DISPLAY ALL (STN format)

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AN      1179439   INFULL  EDP 20250506  ED 20250506 UP 20250513 EDTX 20250513
        DED 20250502 DUPD 20250512 Full-text
TIEN    REUSABLE 3D PRINTER SYSTEM AND METHOD
IN      Pankaj, Department of Computer Science Engineering,
        ChandigarhUniversity, National Highway 05, Chandigarh-Ludhiana Highway,
        Mohali, Punjab-140413, India Mohali
PA      Chandigarh University, Chandigarh University, National Highway 05,
        Chandigarh-Ludhiana Highway, Mohali, Punjab -140413, India. Mohali
PAS     CHANDIGARH UNIVERSITY
LAF     English
LA      English
DT      Patent; (Fulltext)
PI      IN 202511037538        A     20250502
PIT     INA ORDINARY PATENT APPLICATION or CONVENTION PATENT APPLICATION or PCT
        NATIONAL PHASE APPLICATION
STI     ALIVE
AI      IN 2025-11037538               20250418
PRAI    IN 2025-11037538               20250418
IPCI    B33Y0010-00 [A]; B29C0064-118 [A]; B33Y0030-00 [A]; B33Y0040-00 [A];
        A61M0021-00 [A]

ABEN
        Original
        The present invention relates to a reusable 3D printer system,
        comprising a dual-compartment architecture designed for sustainable and
        efficient additive manufacturing. The first compartment is configured to
        generate filament from raw or recycled materials, incorporating
        mechanisms such as a liquid structuring pipe, a motorized pattern
```

generator, and a raw material input unit equipped with weight sensors and a data collection algorithm. The second compartment utilizes the produced filament for 3D printing and features a filament transfer mechanism with roller movements, a precision-controlled heating system governed by a Proportional-Integral- Derivative (PID) algorithm, and a vacuum system regulated by a pressure control algorithm. The filament transfer is further enhanced with tension sensors and a tension control algorithm to prevent stretching or breakage. The system supports closed-loop recycling of filament with quality assurance via a material processing algorithm and includes predictive maintenance algorithms that analyze sensor data to anticipate and prevent potential faults.

DETDEN

[DESC0001] FORM 2

...

[DESC0014] The present invention relates to a reusable 3D printing system and method that focuses on addressing environmental concerns associated with traditional 3D printing practices. The system allows for the sustainable and efficient production of three-dimensional objects by integrating reusable materials and a closed-loop recycling process.

BACKGROUND AND PRIOR ART OF THE INVENTION

...

[DESC0029] It includes a raw material input mechanism with weight sensors and a data collection algorithm to monitor input quantities.

CLMEN

[CLM0001] 1. A reusable 3D printer system comprising a first compartment configured to create filament from raw materials, and a second compartment configured to use said filament.

...

[CLM0010] 10. The reusable 3D printer system as claimed in claim 1 , wherein the motorized system in the first compartment is configured to produce different filament designs based on pre-programmed patterns and user inputs.

Dated this 5th day of April 2025

Agent of the Applicant Chandigarh University ABSTRACT

REUSABLE 3D PRINTER SYSTEM AND METHOD

The present invention relates to a reusable 3D printer system, comprising a dual-compartment architecture designed for sustainable and efficient additive manufacturing. The first compartment is configured to generate filament from raw or recycled materials, incorporating mechanisms such as a liquid structuring pipe, a motorized pattern generator, and a raw material input unit equipped with weight sensors and a data collection algorithm.

The second compartment utilizes the produced filament for 3D printing and features a filament transfer mechanism with roller movements, a precision-controlled heating system governed by a Proportional-Integral-Derivative (PID) algorithm, and a vacuum system regulated by a pressure control algorithm. The filament transfer is further enhanced with tension sensors and a tension control algorithm to prevent stretching or breakage. The system supports closed-loop recycling of filament with quality assurance via a material processing algorithm and includes predictive maintenance algorithms that analyze sensor data to anticipate and prevent potential faults.

Fig. 1.

KT

raw material input; recycled filament; reusable material; sensor data; material processing algorithm; disposable support material; printed object; integrated raw material processing; intelligent control mechanism; maintenance algorithm; tension control algorithm; filament transfer; filament tension; three-dimensional object; pressure control algorithm; efficient production; tension sensor; filament design; material reuse; user input; pre-programmed pattern; recycled material; filament processing; environmental impact; significant material waste; single-use material; unused material; material usage; printing process; future printing cycle

In North America

CAS Customer Center:
P.O. Box 3012
Columbus, Ohio 43210-0012
U.S.A.

Phone: 800-753-4227 (North America)
614-447-3731 (worldwide)
E-mail: help@cas.org
Internet: www.cas.org

In Europe

CAS Customer Center EMEA
represented by
FIZ Karlsruhe - Leibniz-Institute for Information Infrastructure
Hermann-von-Helmholtz-Platz 1
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E-mail: EMEAhelp@cas.org
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Internet: www.jaici.or.jp